

**Interaction of point defects with impurities in the Si-SiO<sub>2</sub> system and its influence on the interface properties**  
**Kropman, Daniel; Mellikov, Enn; Kärner, Tiit; Heinmaa, Ivo; Laas, Tõnu; Londos, Charalampos; Misiuk, Andrzej** Solid state phenomena 2011 / p. 263-266 <https://www.sciencedirect.com/science/article/pii/S0040609009014564>

**Stress relaxation mechanism by strain in the Si-SiO<sub>2</sub> system and its influence on the interface properties**  
**Kropman, Daniel; Mellikov, Enn; Kärner, Tiit; Laas, Tõnu; Medvid, Arthur; Onufrijevs, Pavels; Dauksta, Edvins** Solid state phenomena 2011 / p. 259-262 [https://globaljournals.org/GJSFR\\_Volume17/1-Stresses-Relaxation-Mechanism.pdf](https://globaljournals.org/GJSFR_Volume17/1-Stresses-Relaxation-Mechanism.pdf)